



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : SOPHIE ET AL.) Group Art Unit 2813
 App. No. : 09/975,466)
 Filed : October 9, 2001)
 For : IN SITU REDUCTION OF COPPER)
 OXIDE PRIOR TO SILICON)
 CARBIDE DEPOSITION)
 Examiner : Kielin, E.)

PATENT
 #14/LPS
 5/28/3
 Surler

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
 P.O. Box 1450
 Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing 3 references that are also enclosed. Applicants believe no fee is due because these references were originally cited in an Information Disclosure Statement that was filed before the receipt of a first Office Action on the merits (37 C.F.R. § 1.97(b)(3)). However, if a fee is due, the Commissioner is authorized to charge the fee set forth in 37 C.F.R. § 1.17(p) to Deposit Account No. 11-1410.

Applicants are unable to provide a date of publication for reference publication numbers 2 (SOI Technology, IBM's Next Advance in Chip Design) and 3 (slides from Sundani et al. "Oral Presentation of Dual Damascene Process"). For the purposes of examination, the Examiner is requested to assume that these publications predate the filing of the present application by more than one year. The month of publication is thus not at issue.

Reference number 1 (DE 41 08 73) discloses the removal of copper oxide by a liquid phase treatment, such as with an acidic solution or alcohol. In the case of organic carboxylic acids, copper oxide is dissolved in an acidic solution and forms copper carboxylates that dissolve in the solution.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: May 19, 2003

By: Andrew N. Merickel

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